

DO NOT ENTER: /E.M./

**RESPONSE UNDER 37 CFR §1.116
EXPEDITED PROCEDURE
EXAMINING GROUP 1794**

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Atty. Docket : NL 021426

RALPH KURT ET AL.

Group Art Unit: 1794

Serial No. 10/539,362

Examiner: ELIZABETH E. MULVANEY

Filed: JUNE 15, 2005

CONF. NO. 7350

TITLE: USE OF BI-LAYER PHOTOLITHOGRAPHIC RESISTS AS NEW MATERIAL
FOR OPTICAL STORAGE

Mail Stop AF
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

AMENDMENT AFTER FINAL ACTION UNDER 37 C.F.R. §1.116

Sir:

In response to the Final Office Action of July 25, 2008,
please amend the application and consider the remarks as follows: